

ABSTRACT OF THE DISCLOSURE

The method of manufacturing a thin-film magnetic head in accordance with the present invention comprises the steps of forming a first magnetic pole layer; removing both sides in a track width direction of the first magnetic pole layer so as to leave a predetermined residual area in the first magnetic pole layer; forming an insulating layer about the residual area of the first magnetic pole layer; forming a gap layer made of a nonmagnetic material; forming a second magnetic pole layer magnetically connected to the first magnetic pole; and patterning the second magnetic pole layer by etching while using a mask. As a consequence, even if an area relatively far from the second magnetic pole layer is eliminated from the gap layer, the insulating layer is mainly exposed from this area. This can prevent magnetic materials from adhering to the root of the second magnetic pole layer and its vicinity during etching.